

L4 ANSWER 153 OF 233 CA COPYRIGHT 2003 ACS on STN  
AN 120:198776 CA  
TI Targets of partially stabilized zirconia, and their manufacture  
IN Jaeckel, Gernot; Rudolph, Thomas; Peuckert, Doris; Joennson, Sigurd  
PA Degussa AG, Germany  
SO Ger., 4 pp.  
CODEN: GWXXAW  
DT Patent  
LA German  
IC ICM C23C014-08  
ICS C23C014-30; C04B035-48  
ICA F01D005-18  
CC 57-2 (Ceramics)  
FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	DE 4302167	C1	19940210	DE 1993-4302167	19930127
PRAI	DE 1993-4302167		19930127		

AB The ZrO<sub>2</sub> of the targets contains 0.5-25 wt.% Y<sub>2</sub>O<sub>3</sub> as stabilizer, both oxides have purity .gt; or = .98%, and 5-80 wt.% of the ZrO<sub>2</sub> is present in the monoclinic form and the balance in the tetragonal and cubic form. The targets have d. 3.0-4.5 g/cm<sup>3</sup>, and are used for forming thermally insulating coatings on metal components exposed to high temps. The targets are manufd. by pressing ZrO<sub>2</sub>-Y<sub>2</sub>O<sub>3</sub> mixts., and sintering the green targets at 1150-1450.degree. for 0.5-10 h.

ST yttria stabilizer zirconia sputtering target  
IT Sputtering  
(targets, zirconia, yttria-stabilized, manuf. of,  
for forming thermally insulating coatings on metal components  
exposed to high temps.)  
IT 1314-23-4, Zirconia, uses  
RL: USES (Uses)  
(yttria-stabilized, sputtering targets, for forming thermally  
insulating coatings on metal components exposed to high  
temps.)  
IT 1314-36-9P, Yttria, uses  
RL: PREP (Preparation); USES (Uses)  
(zirconia partially stabilized with, manuf. of, for forming  
thermally insulating coatings on metal components exposed to  
high temps.)

=>  
=> d his

(FILE 'HOME' ENTERED AT 15:52:13 ON 15 SEP 2003)

FILE 'CA' ENTERED AT 15:52:20 ON 15 SEP 2003

L1 87926 S ZIRCONIA OR ZIRCONIUM(W)OXIDE  
L2 4182 S L1 AND CUBIC  
L3 1950 S L2 AND (YTTRIA OR YTTRIUM(2A)OXIDE? OR GADOLIUM OR YTTERBIUM  
L4 233 S L3 AND (COATING OR COAT?)

=>